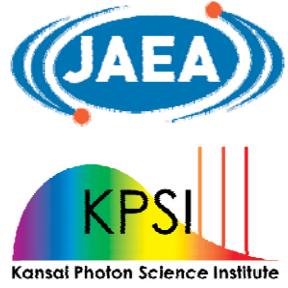


Stable 10 MeV class quasi-mono energetic electron bunch generation by laser wakefield and self- channeling

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Shanghai China**



Joint Research between ILE and KPSI



KPSI JAEA

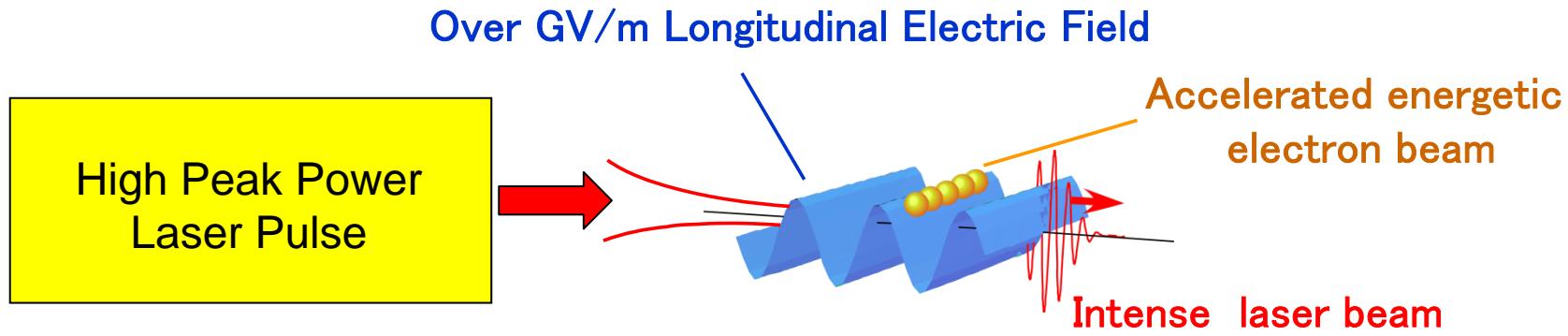
Michiaki Mori, Kiminori Kondo

H. Kotaki, M. Kando, M. Kado, S. Bulanov,
H. Daido

ILE Osaka

Y. Mizuta, K. A. Tanaka, H. Nishimura

Background



Electron plasma wave is excited by intense laser pulse,
and it can generate extreme large acceleration field (TV/m).

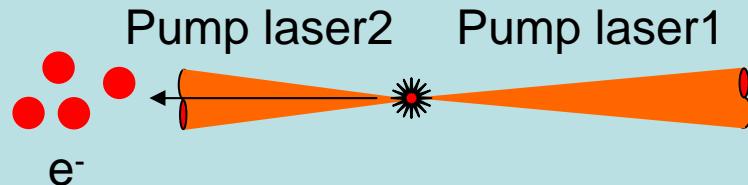
- Compact accelerator → Cancer therapy
- Femtosecond bunch length → Pulse radiolysis
- Good Emittance → e-beam gun
- Wide range tunability → Cancer therapy ·Material development

→ Stable E-beam Generation is required!

How to get a stable acceleration

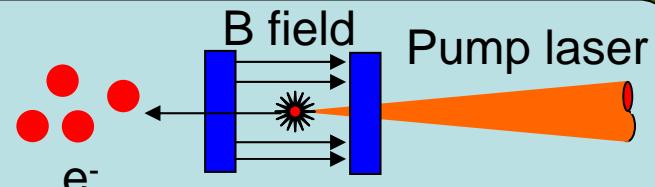
- Colliding-injection

J. Faure et al., Nature **444**, 737 (2006)
H. Kotaki et al., IEEE TPS **36**, 1760 (2008)



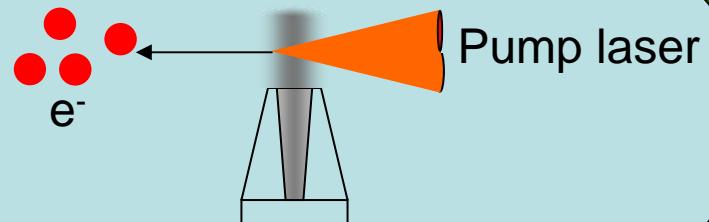
- Magnetized plasma

T. Hosokai et al., PRL **97**, 075004 (2006)



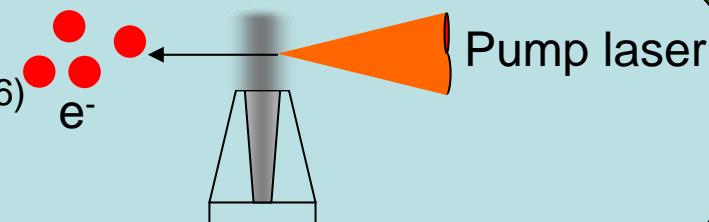
- Density ramp

C.C.D. Geddes et al., PRL **100**, 215004(2008)



- Prepulse control

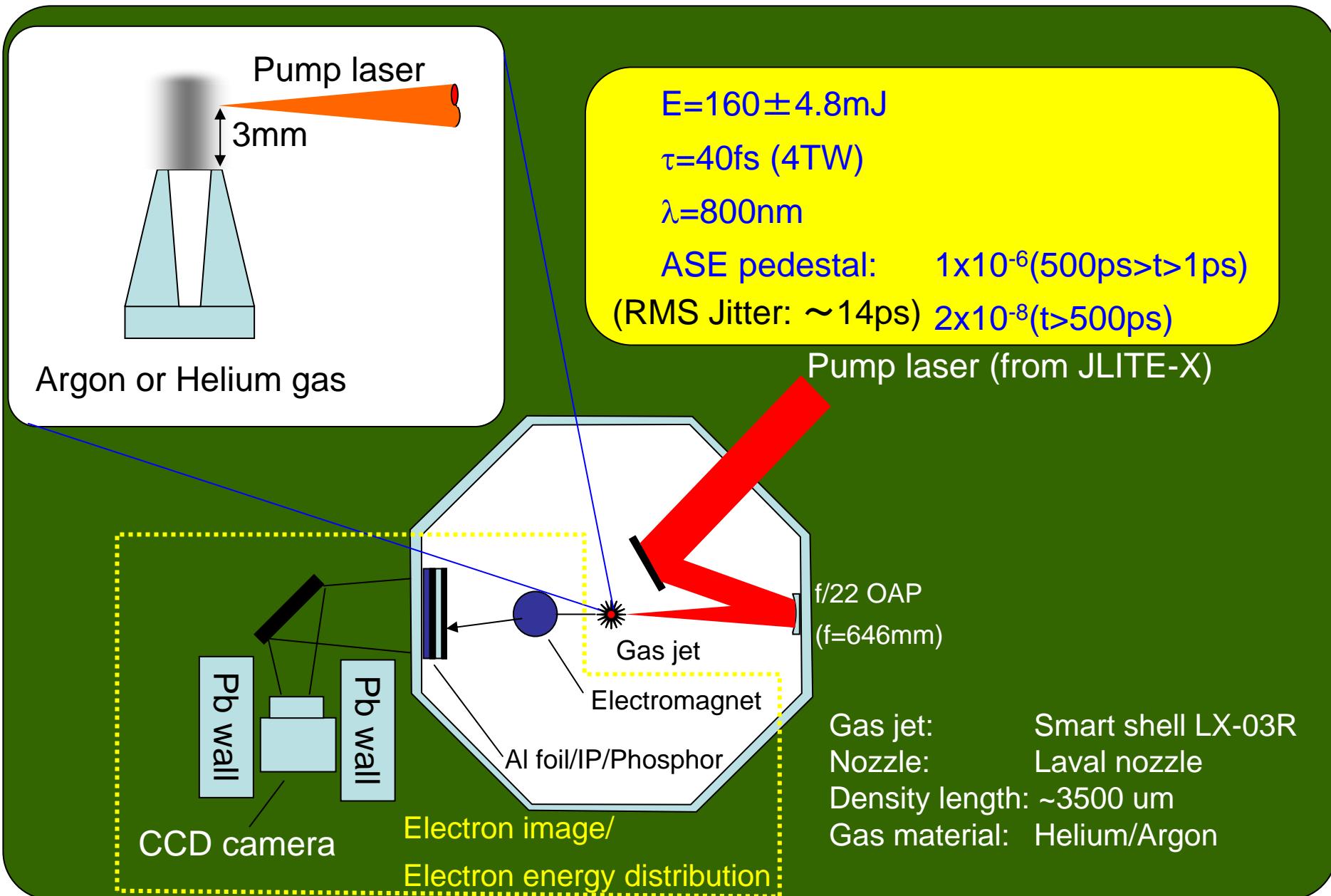
S.P.D. Mangles et al., Plas. Phys. Cont. Fus. **48**, B83 (2006)



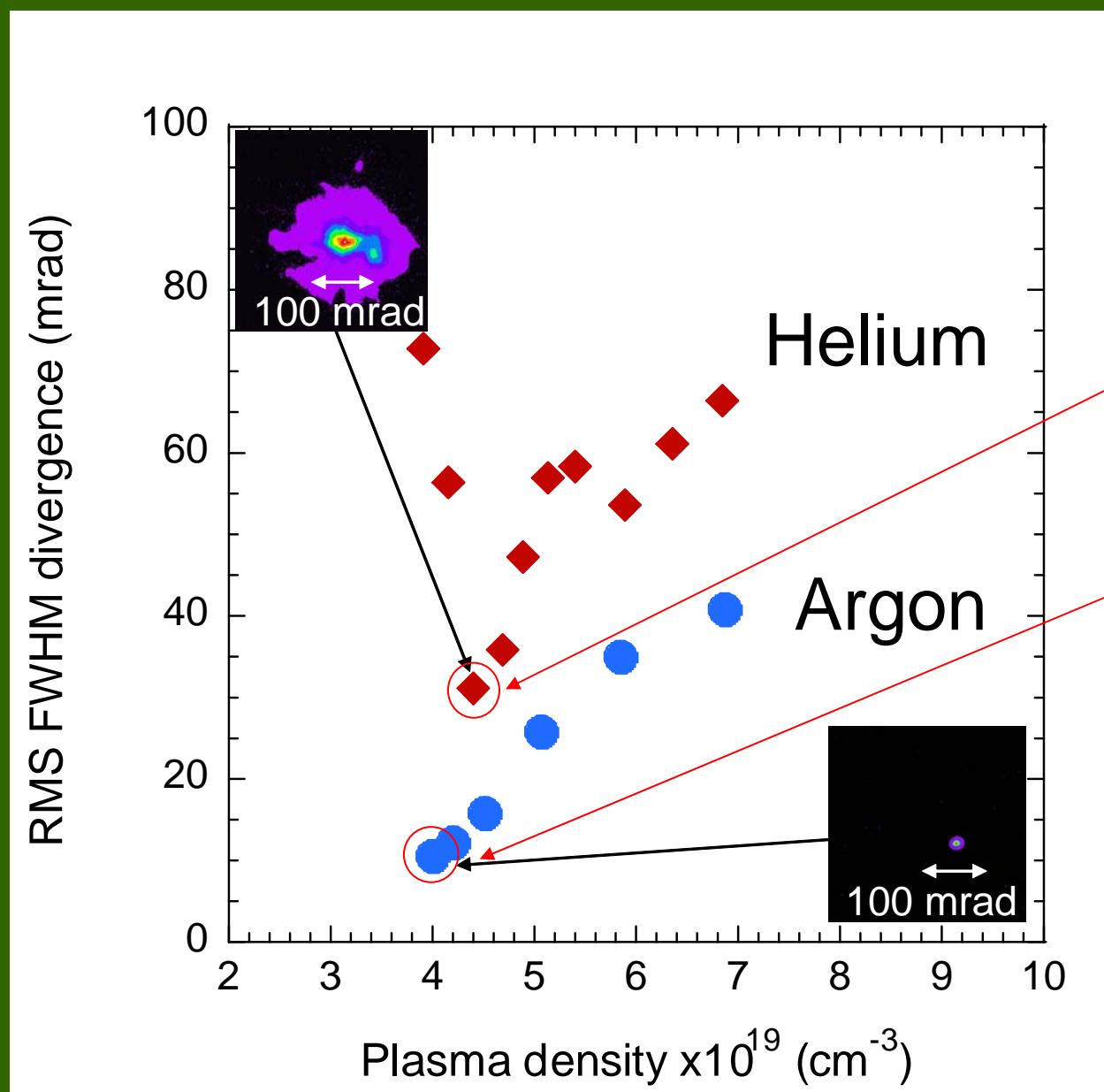
Control a wakefield by laser and target conditions

Gas material dependence (In this work)

Experimental setup



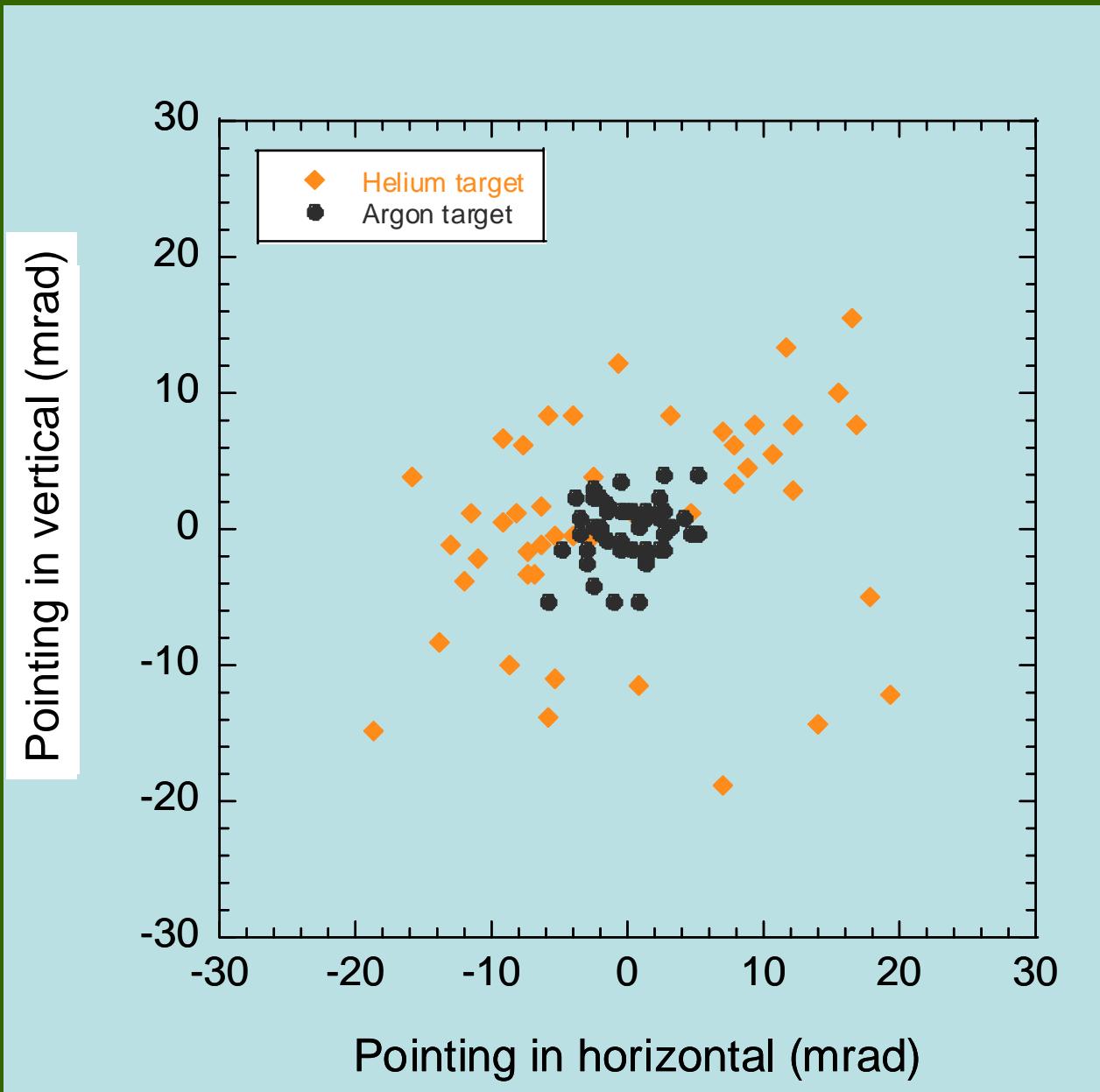
Result(1) e-beam divergence



Beam divergence:
 $\theta_{\min}=31.1 \text{ mrad}@He$

$\theta_{\min}=10.6 \text{ mrad}@Ar$

Result(2) e-beam pointing stability



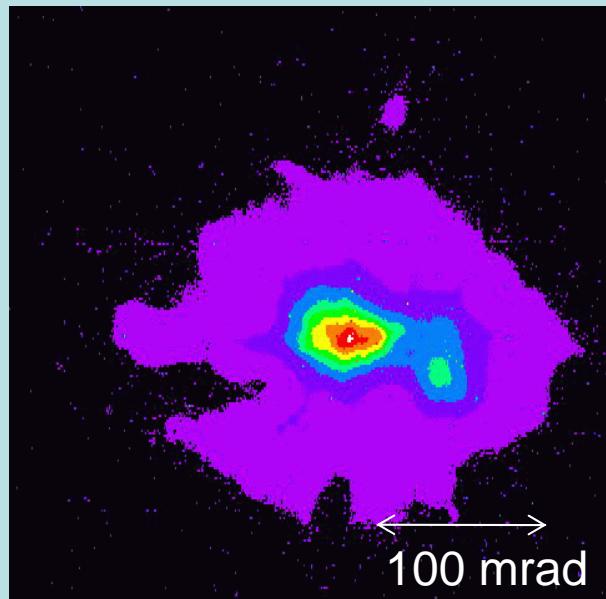
Pointing stability:

$$\theta_{\min} = 2.4 \text{ mrad} @ \text{Ar}$$

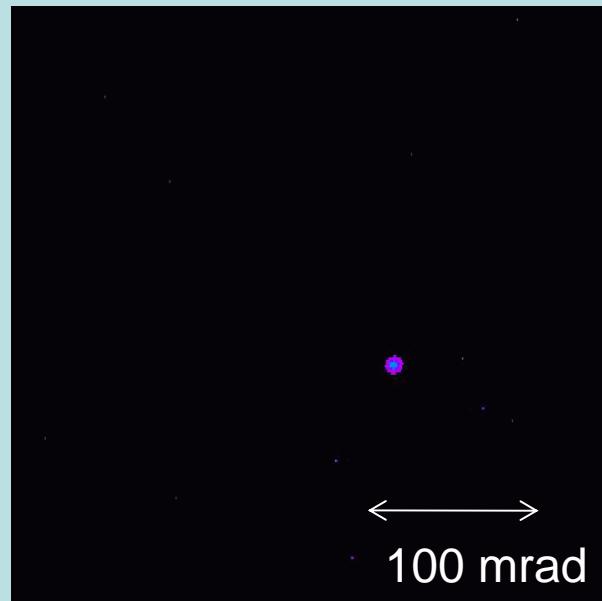
$$\theta_{\min} = 9.8 \text{ mrad} @ \text{He}$$

Result(3) e-beam divergence and pointing stability

Spatial profile of the e-bunch ($>1\text{MeV}$)



Helium target

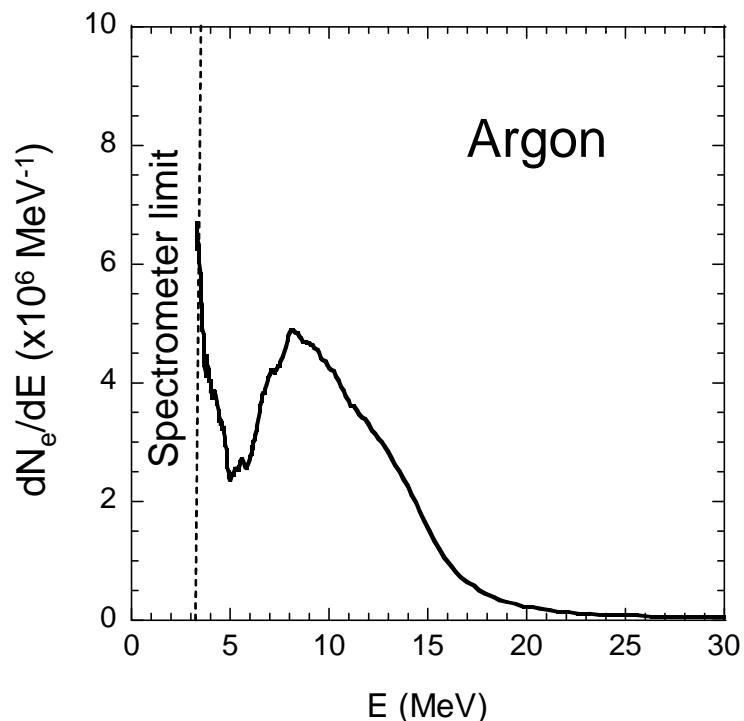
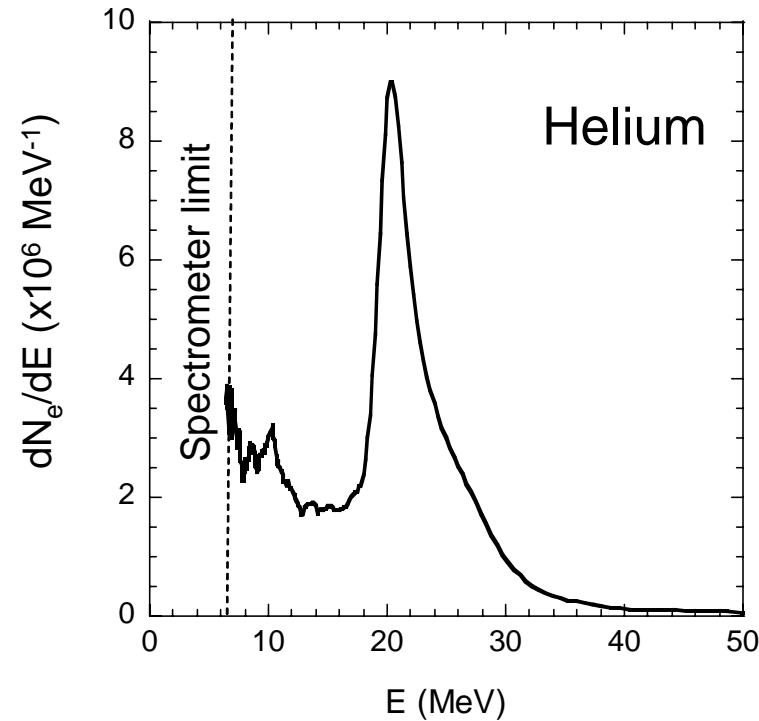


Argon target

Plasma density:

$$n_e \sim 4 \times 10^{19} \text{ cm}^{-3} \text{ (in He and Ar)}$$

Result(4) e-beam energy distribution

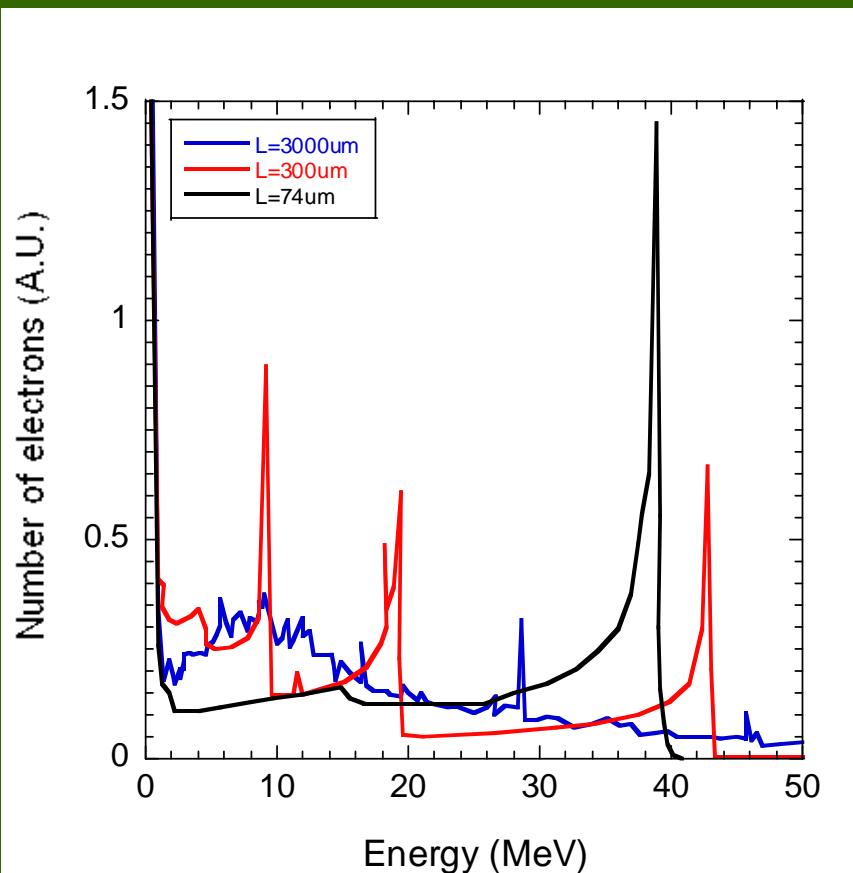


	Helium Target	Argon Target
Peak Energy (MeV)	24.8 ± 3.6	8.5 ± 0.8
Probability of Generation of Q-Mono E-Beam (%)	38	84

Discussion(1): Energy dist./Beam div. • Pointing

1. Energy Distribution

(Acceleration distance dependence)



Nakanii et al., APL 93 081501 (2008).

Broad spectrum could be formed by the multi-dephasing with propagating over the dephasing length

2. Divergence / Pointing stability

Electron injection point

L=short

→Divergence/Pointing: Worth

Electron injection point

L=Long

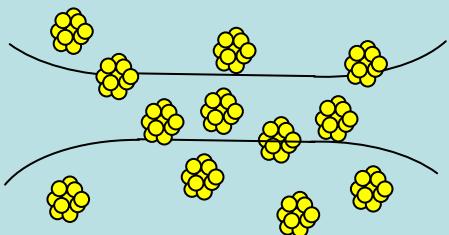
→Divergence/Pointing: Good

$$\Delta\theta \propto \tan^{-1} \frac{d_{wf}}{l_{wf}}$$

d_{wf} : Wakefield spot size
 l_{wf} : Wakefield length

Discussion(2):laser propagation

Cluster



Refractive index of the cluster crowd

$$n_{cluster} = \sqrt{1 + 4\pi n_{cluster} \operatorname{Re} \left| \frac{\epsilon_{cl} - 1}{\epsilon_{cl} + 2} a^3 \right|}$$

n_{cl} : Cluster number density

a : Cluster size

Dielectric constant of the cluster

$$\epsilon_{cl} = 1 - \frac{\omega_p^2}{\omega_L^2 \left(1 + i \frac{\nu_{ei}}{\omega_L} \right)}$$

ω_p : Plasma frequency

ω_L : Laser frequency

ν_{ei} : electron-ion collision frequency

Cluster media induces a positive lens effect by the strong polarization.

Positive lens effect



Assisting a long propagation

I. Alexeev et al., PRL 90 103402 (2003).

$$n_{tot} = \sqrt{1 - \frac{\omega_{p,gas}^2}{\omega_L^2}} + 4\pi n_{cluster} \operatorname{Re} \left| \frac{\epsilon_{cluster} - 1}{\epsilon_{cluster} + 2} a^3 \right|$$

T. Caillaud et al., PoP 13 033105 (2006).

Contribution by Gas

Contribution by Cluster (In He, no contribution)

Summary

- With Ar target, well collimated and pointing stabilized e-beam have been obtained rather than He target, while quasi-mono energetic distribution is also observed.
- These results suggest that a comparatively longer acceleration distance could be realized in Ar.
- With Ar, cluster jet can be formed. Index of cluster mixed media might affect a long propagation of focused laser pulse.

謝 謝 ! !